

ABSTRACT OF THE INVENTION

There is provided a method of manufacturing a mask blank 1 with a resist film, capable of improving in-plane uniformity of a pattern, the method including: preparing a substrate 10 having a thin film 11; forming a resist film 12 on a surface of the thin film 11; and removing a peripheral edge portion of the resist film 12, wherein in the removing, the peripheral edge portion of the resist film 12 is removed so as to impart directions in plan view when the substrate 10 is horizontally mounted, by a positional relation in plan view between the thin film 11 and the resist film 12.

Fig.1